



Universal Remover Products

Organic mixtures designed to remove negative and positive photoresist and other organic compounds when an ultra clean surface is required.

These products provide extended bath life and will not harm most materials used to manufacture semiconductor devices such as photomask plates, pc boards and other related products used in the micro electronics industry. As an additional benefit, the Nophenol products and Universal 1 contain no phenol or chlorinated solvents.

NOPHENOL SERIES

Nophenol EKC922®

Used to remove photoresist over cured or semi-cured polyimide without attack.

Nophenol EKC944™

Designed for use at elevated temperatures for hard-to-remove photoresist layers. Used with a solvent rinse, this product will remove harshly treated photoresist providing extremely clean surfaces as demonstrated by low CV shift.

UNIVERSAL SERIES

EKC712D™

Provides exceptional removal capability of both negative and positive photoresist and can be operated over a wide temperature range.

EKC offers applications engineering support for all products. This includes product development and sustaining engineering solutions. On-site consulting, process evaluation and/or additional wafer testing are available through EKC's applications engineering or R & D as needed.

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DuPont Electronic Technologies

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